

**EXPRESS MAIL LABEL NO. EV314045552US**

**DATED: 27 OCTOBER 2003**

**ATTORNEY DOCKET: FTIS 1004-1**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of Inventors:  
**Christophe Pierrat et al.**

Application No. \_\_\_\_\_

Filed: **27 October 2003 (herewith)**

Title: **Mask Data Preparation**

Group Art Unit: unknown

Examiner: unknown

**CUSTOMER NO. 22470**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.56**

Sir:

It is requested that the information identified in this statement be considered by the Examiner and made of record in the above-identified application. This statement is not intended to represent that a search has been made or that the information cited in the statement is, or is considered to be, material to patentability as defined in 37 C.F.R. 1.56.

Enclosed with this statement is a Form PTO-SB/08. The Examiner is requested to initial the form and return it to the undersigned in accordance with M.P.E.P. 609.

Also enclosed with this statement is a copy of each cited document as required by 37 C.F.R. 1.98. The exception to this, in accordance with the 05 August 2003 Official Gazette Notice in which the USPTO waives the requirement for submitting copies of U.S. Patent and Publications for cases filed after 30 June 2003, is that copies of U.S. Patent documents and copies of U.S. Patent publications are not being submitted.

This statement should be considered under 37 C.F.R. 1.97(b) because it is being filed within three months of the filing date of an application other than a continued prosecution application under 37 C.F.R. 1.53(d).

**Fee Authorization.** The Commissioner is hereby authorized to charge underpayment of any additional fees or credit any overpayment associated with this communication to Deposit Account No. 50-0869 (FTIS 1004-1). A copy of this authorization is enclosed.

Respectfully submitted,

HAYNES BEFFEL & WOLFELD LLP

Date: \_\_\_\_\_

270403

By: \_\_\_\_\_



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PTO/SB/08B (08-00)

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		Application Number			
		Filing Date		27 OCTOBER 2003	
		First Named Inventor		Christophe Pierrat et al.	
		Group Art Unit			
		Examiner Name			
Sheet		2		of 2	
		Attorney Docket Number		FTIS 1004-1	

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	C1	FRENCH, ROGER H., et al., "Fluoropolymers for 157nm Lithography: Optical Properties from VUV Absorbance and Ellipsometry Measurements," SPIE Proceedings, Microlithography 2000, 12 pages.	
	C2	FLAGELLO, DONIS G., et al., "High-numerical-aperture effects in photoresist," Applied Optics 36(34) (1 Dec 1997) 8944-8951.	
	C3	FRENCH, ROGER H., et al., "Materials Design and Development of Fluoropolymers for Use as Pellicles in 157nm Photolithography," Optical Microlithography XIV, Proceedings of SPIE vol. 4346 (2001).	
	C4	PIERRAT, CHRISTOPHE, et al., "The MEF Revisited: Low k1 Effects versus Mask Topography Effects," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (25 Feb 2003).	
	C5	CHIBA, YUJI, et al., "New generation projection optics for ArF lithography," Optical Microlithography XV, Proceedings of SPIE Vol. 4691 (2002), 679-686.	
	C6	BAEK, SO-YEON, et al., "Simulation Study of Process Latitude for Liquid Immersion Lithography," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (27 Feb 2003), 11 pages.	
	C7	PENDRY, J.B., et al., "Near-field lenses in two dimensions," J. Phys.: Condens. Matter 14 (2002) 8463-8479.	
	C8	OBER, CHRISTOPHER K., "Polymer Surfaces and Surface Analysis," Nanobiotechnology MSE 563/AEP 663 (2000), 43 pages.	
	C9	HAFEMAN, SCOTT, et al., "Simulation of imaging and stray light effects in immersion lithography," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (27 Feb 2003), 13 pages.	

Examiner Signature		Date Considered	
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			Application Number		
			Filing Date		
			First Named Inventor		
			Group Art Unit		
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			Attorney Docket Number		
Sheet	1	of	2	FTIS 1004-1	

U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code <sup>2</sup> (if known)			
	A1	5,121,256		Corle et al.	06-09-1992	
	A2	5,469,299		Nagano	11-21-1995	
	A3	5,982,558		Further et al.	11-09-1999	
	A4	6,198,576		Matsuyama	03-06-2001	
	A5	6,522,484		Schuster	02-18-2003	
	A6					
	A7					
	A8					
	A9					
	A10					
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FOREIGN PATENT DOCUMENTS								
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